

6/12/01

Commissioner for Patents
Washington, D.C. 20231

Prior to examination, please amend the application as follows:

Please delete the current Title and insert the following:

--METHOD AND APPARATUS FOR DETERMINING POLISHING ENDPOINT
WITH MULTIPLE LIGHT SOURCES--

At page 1, line 6, insert the following paragraph:

The present application is a continuation of U.S. Patent Application Serial No.

09/237,472, filed January 25, 1999.

now US. Patent No. 6,247,998

Cancel claims 24-33, 35 and 46-54.

Amend claims 1, 36, 43, 45 and 58 as follows:

1. (Amended) An apparatus for use in chemical mechanical polishing a substrate, comprising:

a first optical system including a first light source to generate a first light beam to impinge on the substrate, the first light beam having a first effective wavelength, and a first

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